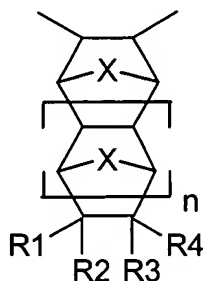


## Amendments to the Abstract

Please replace the Abstract with the following amended Abstract:

### ABSTRACT

The disclosed invention relates to novel norbornene-type monomers containing pendent lactone or sultone groups. The invention also relates to norbornene-type polymers and copolymers comprising one or more repeating units represented by the formula:



and containing pendent lactone or sultone groups. These polymers and copolymers are useful in making photoimageable materials. The photoimageable materials are particularly suitable for use in photoresist compositions useful in 193 and 157 nm photolithography.